2025-02-13(목), 10:55-12:40
좌장: 추후업데이트 예정

D. Thin Film Process Technology 분과

[TE2-D] Memory Capacitors

TE2-D-1 10:55-11:10	**Investigation of Atomic Layer Deposited SnO_2 Thin Films for Next-Generation DRAM Electrode Application** InHong Hwang[1,2] and In-Hwan Baek[1,2] 1Department of Chemistry and-Chemical Engineering, Inha University, [2]Program in Semiconductor Convergence, Inha University
TE2-D-2 11:10-11:25	**Achieving Equivalent Oxide Thickness Scaling of ZrO_2 Dielectric Thin Film via Gd Doping without Sacrificing Tetragonal Crystallinity** Seungwoo Lee[1,2], Jihun Nam[1,2], Yoona Choi[1,2], Jonghwan Jeong[1,2], Min Kyeong Nam[1,2], Hansol Oh[3], Hanbyul Kim[3], Yongjoo Park[3], Youngjin Kim[4], and Woojin jeon[1,2] [1]Department of Advanced Materials Engineering for Information and Electronics, Kyung Hee University, [2]Integrated Education Program for Frontier Science & Technology, Kyung Hee University, [3]Advanced Research Development Team, SK Trichem Co., Ltd., [4]Department of Chemical Engineering, Kyonggi University
TE2-D-3 11:25-11:40	**Influence of Zr-Precursor Ligands on the Growth and Capacitor Properties of ZrO_2 Thin Films Grown by ALD** Hyeongjun Kim[1], Haram Yang[2], and Woongkyu Lee[1,2] [1]Department of Green Chemistry and Materials Engineering, Soongsil University, [2]Department of Materials Science and Engineering, Soongsil University
TE2-D-4 11:40-11:55	**Strategy for Stabilizing Metastable Rutile-Structured TiO_2 without Substrate Crystallographic Limitations** Jihoon Jeon[1,2] and Seong Keun Kim[1,2] [1]Electronic Materials Research Center, KIST, [2]KU-KIST Graduate School of Converging Science and Technology, Korea University
TE2-D-5 11:55-12:10	**High Performance TiO_2-based DRAM Capacitors with Ultrathin ALD Sn-Doped MoO_2Buffer Layer** Jae Hyeon Lee and Jeong Hwan Han Department of Materials Science and Engineering, Seoul National University of Science and Technology

TE2-D-6 12:10-12:25	**Dielectrics with Sub-surface Dopant Implantation-Mediated Lattice Relaxation and V_O Annihilation via Chemo-physical Plasma Annealing** Gyuha Lee[1], Hyongjune Kim[1], Geongu Han[2], Sangwon Lee[3], Jeongmin Oh[3], and Jihwan An[1,3] [1]Department of Mechanical Engineering, POSTECH, [2]Department of Manufacturing Systems and Design Engineering, Seoul National University of Science and Technolog, [3]Graduate School of Semiconductor Technology, POSTECH
TE2-D-7 12:25-12:40	**Synthesis of Perovskite $SrTiO_3$ Thin Films by Atomic Layer Deposition of SrF_2 and TiO_2** Jaejun Lee, Sangyeon Jeong, and Woongkyu Lee Department of Materials Science and Engineering, Soongsil University